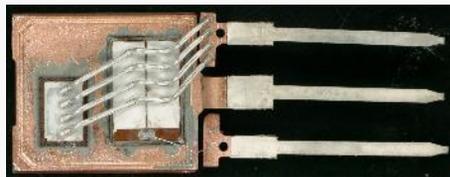
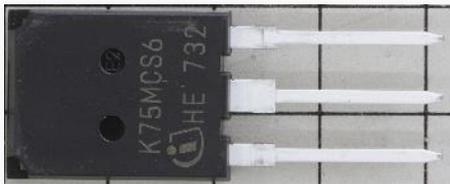
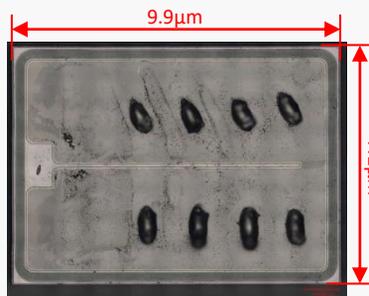


## INFINEON IGBT6(IKQ75N120CS6XKSA1) STRUCTURE ANALYSIS REPORT

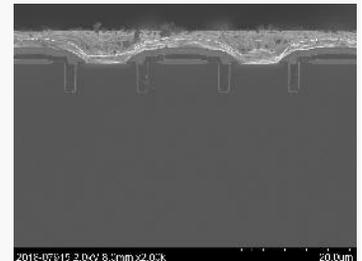
**January 2018.** LTEC Corporation released a detailed structure and process analysis report of the latest generation 1200V IGBT high speed device from Infineon. The previous version of this device is IGBT4. It is announced that this is the first power device produced in 12 inch Si wafer.



Package



Die image



SEM-Cross section

### Analysis result summary

1. The gate oxide film is thinner by 14% in order to improve the transconductance compared with the previous generation IGBT4 (1200V high speed 3).
2. The whole transistor cell pitch is reduced by about 9%.
3. The performance of  $V_{ce(sat)}$ , turn-on switching loss power and transconductance are improved.

The report has two individually purchasable sections: a 106-page Structure Analysis Section, and a 28-page Process Analysis section. The Structure Analysis Section reveals the physical construction of the device, including EDX materials analysis, and many other fine details. The Process Analysis Section includes manufacturing process flow and the estimated number of photo masking steps.

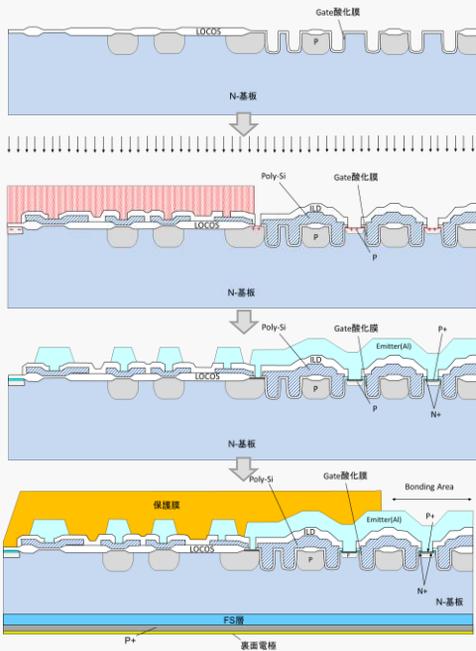
Contact LTEC Corporation for the current price as it decreases over time

18G-0017-1

# Comparison table(IGBT4(HighSpeed3),IGBT5 &IGBT6)

		IGBT4 (HighSpeed3)	IGBT5	IGBT6
Part Number	Unit	IKQ75N120CH3	FF1200R12IE5	IKQ75N120CS6X
Transistors per Switch		1	8	1
Die size [mm xmm]		11.4x7.0	15.6 x7.8	9.9x7.1
Die size	mm2	79.93	121.7	69.72
<b>Electrical Characteristics</b>				
Collector-emitter voltage	V	1200	1200	1200
DC collector current Tc=25°C	A	150	-	150
DC collector current Tc=100°C	A	75	150 ※Tc=80°C	75
Nominal Current Density Ic/A Tc=25°C	A/mm2	1.9	-	2.2
Nominal Current Density Ic/A Tc=100°C	A/mm2	0.94	1.2 ※Tc=80°C	1.1
Max Operating Temperature Tjop	°C	175	175	175
Collector-emitter saturation voltage Tc=25°C	V	2	1.7	1.85
Gate threshold voltage Vth	V	5.8	5.8	5.7
Input capacitance	pF	4856.0	8187.5	4900.0
Output capacitance	pF	505.0	-	360.0
Reverse transfer capacitance	pF	290.0	325	225.0
Transconductance	S	26.0	-	60.0
Turn-on delay time, inductive load tdon	us	0.034	0.2	0.034
Rise time, inductive load	us	0.047	0.16	0.044
Turn-off delay time, inductive load	us	0.282	0.48	0.3
Fall time, inductive load	us	0.029	0.08	0.031
Turn-on energy loss per pulse per IGBT Eon/N/A	mJ/mm2	0.080	0.08	0.074
Turn-off energy loss per pulse per IGBT Eoff/N/A	mJ/mm2	0.035	0.13	0.042
Short-Circuit Current per IGBT Isc/N/A	A/mm2	-	4.1	-
Normalized Thermal resistance, junction to case IGBT	°C·mm2/W	-	27.9	-

## INFINEON IGBT6 manufacturing process sequence



Mask	Process step	Comment
	Wafer	Si FZ N-type substrate N(~50-60Qcm)
[1]	AM Ph 1 <sup>st</sup> oxide	arks
[2]	PD·GF	
	P(11B Anneal CVD S	
[3]	FOX P SiN/SiC FOX O SiN·O	
[4]	TR Phc TR Si ε TR Oxi	ate Oxide
[5]	PolySi GP Ph PolySi GP Ma	
[6]	PCH P	k
[7]	PCH (1 PW Ph	
	Pwell(1 Anneal CP Phc	
[8]	P(11B·	
[9]	N+ Photo/mask	N + Source diffusion



LTEC Corporation US Representative Office  
No.203 2880 Zanker Road San Jose, CA 95034

Phone: (408) 489-1994  
www.ltecusa.com Contact: info@ltecusa.com

## Comparison table(IGBT4(HighSpeed3),IGBT5 &IGBT6)

		IGBT4 (HighSpeed3)	IGBT5	IGBT6
Part Number	Unit	IKQ75N120CH3	FF1200R12IE5	IKQ75N120CS6X
· Transistors per Switch		1	8	1
Die size [mm xmm]		11.4x7.0	15.6 x7.8	9.9x7.1
Die size	mm <sup>2</sup>	79.93	121.7	69.72
<b>Electrical Characteristics</b>				
Collector-emitter voltage	V	1200	1200	1200
DC collector current Tc=25°C	A	150	-	150
DC collector current Tc=100°C	A	75	150 ※Tc=80°C	75
Nominal Current Density Ic/A Tc=25°C	A/mm <sup>2</sup>	1.9	-	2.2
Nominal Current Density Ic/A Tc=100°C	A/mm <sup>2</sup>	0.94	1.2 ※Tc=80°C	1.1
Max Operating Temperature Tjop	°C	175	175	175
Collector-emitter saturation voltage Tc=25°C	V	2	1.7	1.85
Gate threshold voltage Vth	V	5.8	5.8	5.7
Input capacitance	pF	4856.0	8187.5	4900.0
Output capacitance	pF	505.0	-	360.0
Reverse transfer capacitance	pF	290.0	325	225.0
Transconductance	S	26.0	-	60.0
Turn-on delay time, inductive load tdon	us	0.034	0.2	0.034
Rise time, inductive load	us	0.047	0.16	0.044
Turn-off delay time, inductive load	us	0.282	0.48	0.3
Fall time, inductive load	us	0.029	0.08	0.031
Turn-on energy loss per pulse per IGBT Eon/N/A	mJ/mm <sup>2</sup>	0.080	0.08	0.074
Turn-off energy loss per pulse per IGBT Eoff/N/A	mJ/mm <sup>2</sup>	0.035	0.13	0.042
Short-Circuit Current per IGBT Isc/N/A	A/mm <sup>2</sup>	-	4.1	-
Normalized Thermal resistance, junction to case IGBT	°C·mm <sup>2</sup> /W	-	27.9	-

12.8

11.8

# Table of Contents

## Structure Analysis Report

	<b>Page</b>
<b>Device summary</b>	
Table 1, Executive Summary	3
<b>Analysis result summary</b>	4
Table 2. Device structure	5
Table 3. Material	6
Table 4. Package structure	7
<b>Package overview</b>	9
<b>IGBT die overview</b>	12
<b>Si FWD die overview</b>	13
<b>Package structure details</b>	14
<b>Si IGBT analysis</b>	
Plan view (optical microscope)	34
Plan view, Scanning Electron Microscope (SEM)	58
Cross-sectional structure analysis (SEM)	65
<b>Electric characteristic</b>	
IC-Vce	86
Off-State Collector current	87
Breakdown voltage BVces at off mode	88
<b>Appendix</b>	
EDX results	89

# Table of Contents

## Process Analysis Report

	Page
<b>Analysis summary</b>	3
Comparison summary (Infineon 4 <sup>th</sup> gen, 5 <sup>th</sup> gen. & 6 <sup>th</sup> gen.)	4
Package structure (Overview)	5
Die overview	6
<b>Device structure Si IGBT</b>	
Plan analysis	7
Cross section	8
Cell	10
Layout	17
<b>Process flow (estimation)</b>	
Si IGBT front-end wafer process, estimated manufacturing flow	21
Photo/masking steps	
Si IGBT process sequence cross-sectional view	22
<b>Evaluation of electrical characteristics</b>	
I <sub>c</sub> -V <sub>ce</sub> (ON-state)	28
Collector voltage (V <sub>ce</sub> ) and temperature dependence of off-state collector current. Extraction of activation energy (E <sub>a</sub> )	29
<b>Appendix</b>	
References	33
Patents	33